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APPLICATION NO.	FILI	NG DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
09/720,761	03/	/26/2001	Franz Laermer	10191/1629	5642
26646	7590	12/30/2004		EXAMINER	
KENYON & ONE BROAL		N	CHEN, KIN CHAN		
NEW YORK		04		ART UNIT	PAPER NUMBER
	•			1765	

DATE MAILED: 12/30/2004

Please find below and/or attached an Office communication concerning this application or proceeding.

		Application No.	Ameliaanata	{				
		Application No.	Applicant(s)	V.				
	Office Action Commons	09/720,761	LAERMER ET AL.					
	Office Action Summary	Examiner	Art Unit					
	- <del>-</del>	Kin-Chan Chen	1765					
Period fo	The MAILING DATE of this communication a or Reply	ppears on the cover she t with the	correspondence address	·				
THE - Exte after - If the - If NC - Failt Any	ORTENED STATUTORY PERIOD FOR REP MAILING DATE OF THIS COMMUNICATION nsions of time may be available under the provisions of 37 CFR of SIX (6) MONTHS from the mailing date of this communication. e period for reply specified above is less than thirty (30) days, a reproduction of the provision of the period for reply is specified above, the maximum statutory period returned by within the set or extended period for reply will, by static reply received by the Office later than three months after the mailed patent term adjustment. See 37 CFR 1.704(b).	1.  1.136(a). In no event, however, may a reply be timely within the statutory minimum of thirty (30) day do will apply and will expire SIX (6) MONTHS from the, cause the application to become ABANDONE.	mely filed  ys will be considered timely.  the mailing date of this communication.  ED (35 U.S.C. § 133).					
Status								
1) 又	Responsive to communication(s) filed on 19	November 2004.						
		nis action is non-final.						
3)□	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.							
Disposit	ion of Claims							
5)⊠ 6)⊠ 7)□	Claim(s) 19,21-24 and 27-40 is/are pending 4a) Of the above claim(s) is/are withdred claim(s) 19,21-24,27-36,39 and 40 is/are alled claim(s) 37 and 38 is/are rejected. Claim(s) is/are objected to. Claim(s) are subject to restriction and	rawn from consideration. owed.						
Applicat	ion Papers							
9)[	The specification is objected to by the Examin	ner.						
10)	10) ☐ The drawing(s) filed on is/are: a) ☐ accepted or b) ☐ objected to by the Examiner.							
	Applicant may not request that any objection to the	e drawing(s) be held in abeyance. Se	e 37 CFR 1.85(a).					
11)	Replacement drawing sheet(s) including the correction of the oath or declaration is objected to by the l							
Priority (	under 35 U.S.C. § 119							
12)[ a)	Acknowledgment is made of a claim for foreign All b) Some * c) None of:  1. Certified copies of the priority documents.  2. Certified copies of the priority documents.  3. Copies of the certified copies of the priority application from the International Buresee the attached detailed Office action for a list	nts have been received.  nts have been received in Applicat  iority documents have been receive  au (PCT Rule 17.2(a)).	ion No ed in this National Stage					
		•						
AM1	M-1	·						
Attachmen  1) Notice	t(s) e of References Cited (PTO-892)	4) 🗍 Interview 6	(PTO 412)					
	e of References Cited (PTO-692) e of Draftsperson's Patent Drawing Review (PTO-948)	4)  Interview Summary Paper No(s)/Mail D	ate					
3) 🔲 Infori	mation Disclosure Statement(s) (PTO-1449 or PTO/SB/06 r No(s)/Mail Date	5) ☐ Notice of Informal F 6) ☐ Other:	Patent Application (PTO-152)					

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### **DETAILED ACTION**

## Claim Rejections - 35 USC § 103

- 1. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
  - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 2. Claims 37 and 38 are rejected under under 35 U.S.C. 103(a) as obvious over Sony (EP 0 414 372 A2).

Sony teaches a method of anisotropic plasma etching a defined structure in as silicon substrate using a process gas. Sony teaches adding a fluorine-delivering etching gas to the process gas. The fluorine-delivering etching gas may include CIF<sub>3</sub>. Sony also teaches that plasma in a wide range of gas mixtures including SiF<sub>4</sub>, Cl<sub>2</sub>/ O<sub>2</sub>, and Cl<sub>2</sub>/ N<sub>2</sub> can be used to supply fluorine atoms for selective isotropic silicon etching. The said gas mixtures can deposit protective layer (so-called precipitating at least one passivating material in the instant claims), (col.1 (page 2), lines 41-48; Col. 4 (page 3), lines 7-17). Sony teaches using dry etching to from a desired configuration in the silicon substrate. Sony is not particular about the desired configuration. Hence, it would have been obvious to one with ordinary skilled in the art to etch a laterally defined structure because it is one of the most popular structure in the semiconductor device fabrication.

## Response to Arguments

3. Applicant's arguments (November 19, 2004) with respect to claims 37-40 have been fully considered but they are not persuasive.

Applicant has argued that the prior art teaches using  $Cl_2/O_2$  or  $SiCl_4 / O_2$  not teaches the addition of compounds including oxygen. It is not persuasive.  $Cl_2/O_2$  or  $SiCl_4 / O_2$  of the prior art comprises oxygen. Furthermore, applicant's claimed invention does not preclude  $Cl_2$  or  $SiCl_4$  in the compound.

### Conclusion

- 4. Claims 19, 21-24, 27-36, 39, and 40 are allowed.
- 5. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure. Pu et al. (US 5,843,847; col. 1, line 62 through col. 2, line 4) teaches that fluorocarbon gas containing  $C_2F_6$  forms polymeric by products that deposits as a passivating layer.
- 6. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Kin-Chan Chen whose telephone number is (571) 272-1461. If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nadine Norton can be reached on (571) 272-1465. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

December 23, 2004

Kin-Chan Chen Primary Examiner Art Unit 1765

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